

Docket No.: SHIGA7.054APC

CONSIDERED: /P.T.R./ **10/589681 Rec'd PCT/PTO 16 AUG 2006**

INFORMATION DISCLOSURE STATEMENT

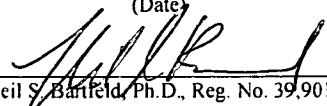
Applicant : Ogata et al.
App. No : Unknown
Filed : Herewith
For : POLYMER COMPOUND,
PHOTORESIST COMPOSITION
INCLUDING THE POLYMER
COMPOUND, AND RESIST
PATTERN FORMATION METHOD
Examiner : Unassigned
Art Unit : Unknown

CERTIFICATE OF MAILING

I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

August 16, 2006

(Date)


Neil S. Bartfeld, Ph.D., Reg. No. 39,901

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 5 references to be considered by the Examiner. Also enclosed are 3 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

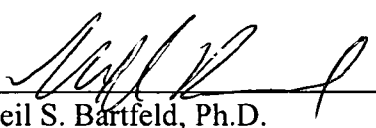
This Information Disclosure Statement is being filed within three months of the filing date, with an RCE or before receipt of a first office action after an RCE and no fee is required.

The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment, to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: August 16, 2006

By: 
Neil S. Bartfeld, Ph.D.
Registration No. 39,901
Agent of Record
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ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /P.T.R

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application No.	Unknown 10/589681
	Filing Date	Herewith 10/589681
	First Named Inventor	Toshiyuki Ogata
	Art Unit	Unknown 1795
(Multiple sheets used when necessary)	Examiner	Unassigned Ponder Thompson-Rummel
SHEET 1 OF 1	Attorney Docket No.	SHIGA7.054APC

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
/P.T.R./	1	2002/0177068 A1	11-28-2002	Park et al.	
/P.T.R./	2	6,329,125 B2	12-11-2001	Takechi et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹

NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.		T ¹
/P.T.R./	3	Hagiwara et al. "Characterization of Fluoropolymer Resist for 157-nm Lithography." <i>Journal of Photopolymer Science and Technology</i> . 16(4):557-564 (2003).		
/P.T.R./	4	Houlihan et al. "New Fluorinated Resins for 167nm Lithography Application." <i>Journal of Photopolymer Science and Technology</i> . 16(4):581-590 (2003).		
/P.T.R./	5	Kawaguchi et al. "Dry-Etching Resistance for Fluoropolymers for 157-nm Single-Layer Resists." <i>Proceedings of SPIE</i> . 5039:43-52 (2003).		

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Examiner Signature	/Ponder Thompson Rummel/	Date Considered	06/18/2008
<p>*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>			

T¹ Place a check mark in this area when an English language Translation is attached.

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /P.T.R./